

## Refine Search

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### Search Results -

Terms	Documents
L1 and (implant same (RTN or thermal nitridation))	11

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**Database:**

- US Pre-Grant Publication Full-Text Database
- US Patents Full-Text Database
- US OCR Full-Text Database
- EPO Abstracts Database
- JPO Abstracts Database
- Derwent World Patents Index
- IBM Technical Disclosure Bulletins

**Search:**

Search

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### Search History

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DATE: Thursday, March 17, 2005 [Printable Copy](#) [Create Case](#)

<u>Set Name</u> <u>Query</u>	<u>Hit Count</u>	<u>Set Name</u>
		result set
<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>		
<u>L10</u> L1 and (implant same (RTN or thermal nitridation))	11	<u>L10</u>
<u>L9</u> L8 and RTN	3	<u>L9</u>
<u>L8</u> L1 and "ghyka"	426	<u>L8</u>
<u>L7</u> L6 and "ghyka"	0	<u>L7</u>
<u>L6</u> L5 and RTN	20	<u>L6</u>
<u>L5</u> (438/791-794).ccls.	676	<u>L5</u>
<u>L4</u> L1 and ((RTN or thermal nitridation) same silicon same trench)	27	<u>L4</u>
<u>L3</u> L1 and ((RTN or thermal nitridation) same silicon)	442	<u>L3</u>
<u>L2</u> L1 and (RTN or thermal nitridation)	758	<u>L2</u>
<u>L1</u> (438/\$).ccls.	167846	<u>L1</u>

END OF SEARCH HISTORY